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# High-Performance Midwave Type-II Superlattice Infrared Photodetectors With a Stepped InAs/GaSb Absorber

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Abstract—Due to the short carrier diffusion length, the extraction of photogenerated carriers is one of the key issues in InAs/GaSb superlattice (SL) photodetectors. Here, we report a midinfrared InAs/GaSb SL absorber with a stepped band alignment. The stepped absorber facilitates a better carrier extraction efficiency. Simulation results show that the proposed nBn detector with a stepped absorber exhibited a substantial performance improvement over the nBn detectors with uniform absorbers. At 150 K, the detector with a 3.6- $\mu$ m-thick stepped absorber has a maximum quantum efficiency (QE) of  $\sim\!$ 46%, which is about 16% higher than that of the detectors with uniform absorbers. The maximum specific detectivity reached  $\sim$ 4.26 imes 10 $^{10}$  cm·Hz $^{1/2}$ /W at 4.9  $\mu$ m under -0.2 V bias. With the enhanced carrier extraction efficiency, the detectivity can gained a further improvement with a thicker stepped absorber, unlike the detector with a uniform absorber where the detectivity deteriorated with the absorber thickness increased from 3.6 to 4.2  $\mu$ m.

Index Terms—InAs/GaSb, nBn photodetector, quantum efficiency (QE), type-II superlattices (T2SLs).

#### I. INTRODUCTION

TYPE-II superlattices (T2SLs) have attracted great attention for the development of high-performance infrared photodetectors, especially for midwave infrared (MWIR)

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detection applications, including night vision, infrared imaging, and infrared guidance [1], [2], [3]. Motivated by the tunable bandgap, large carrier effective mass, low Auger recombination rate, and high material uniformity [4], [5], [6], T2SLs, and in particular InAs/GaSb superlattices (SLs), serve as an alternative to the well-established HgCdTe (MCT) and InSb for high operating temperature (HOT) MWIR infrared photodetectors [7], [8].

InAs/GaSb-based focal plane arrays have shown excellent performance in the MWIR spectral regions [1], [9], [10], [11]. However, the relatively high noise and restricted extraction capacity of photogenerated carriers from the active region greatly limit the further performance improvement of MWIR InAs/GaSb detectors. First, the diffusion current, generation-recombination (G-R) dark current associated with the Shockley-Read-Hall (SRH) recombination, trap-assisted tunneling current, and leakage current via surface states of the sidewalls are the main mechanisms of noise dark currents, which greatly degrade the overall device performance [12]. Since the barrier architecture was put forward [13], it has been extensively applied to InAsSb, MCT, and T2SLs photodetectors [3], [14], [15], [16], [17]. With the insertion of wide bandgap barrier layers, the surface leakage current can be effectively eliminated. In addition, the depletion region is almost confined in the wide bandgap barrier layers, by which the G-R dark current is significantly suppressed [10], [18]. As a result, benefiting from bandgap engineering, InAs/GaSb SLs barrier photodetectors exhibit significantly low dark current density compared to conventional devices with p-n or p-i-n architectures [3], [10]. Second, one major disadvantage of InAs/GaSb SLs is the short minority carrier lifetime compared with MCT and InSb [19], [20], resulting in a short carrier diffusion length [21]. A short carrier diffusion length certainly inhibits the extraction of photogenerated carriers from the active layers, making it a key issue for realizing high quantum efficiency (QE) of InAs/GaSb SLs photodetectors. Therefore, limited by the carrier transport, high detection performance cannot be achieved by increasing the thickness of the InAs/GaSb active layers. Consequently, to obtain a highperformance MWIR InAs/GaSb SLs detector, it is essential to suppress the dark current and enhance the transport of photogenerated carriers.

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Parameter	Symbol (unit)	InAs	GaSb	Al <sub>x</sub> Ga <sub>1-x</sub> Sb
Lattice constant	a (Å)	6.0522	6.0854	6.0854+0.0443x
Bandgap at 150 K	$E_{g}(eV)$	0.391	0.780	0.78 + 0.886x
Spin-orbit split-off energy	$\Delta (eV)$	0.39	0.76	/
Electron effective mass	$m_e/m_0$	0.030	0.042	0.042 + 0.188x
Hole effective mass	$m_h/m_0$	0.414	0.412	0.412 + 0.356x
Luttinger parameters				
	$\gamma_1$	20.0	13.4	/
	$\gamma_2$	8.5	4.7	/
	$\gamma_3$	9.2	6.0	/
Optical matrix parameter	$E_{p}$ (eV)	21.5	22.4	/
Valence band offset (w.r.t. GaSb)	VBO (eV)	-0.56	0	-0.38x
<b>Deformation potentials</b>				
<u>-</u>	a <sub>c</sub> (eV)	-5.08	-7.5	/
	$a_{v}(eV)$	-1	-0.8	/
	b (eV)	-1.8	-2	/
Elastic stiffness constant	•			
	$C_{11}$ (10 <sup>11</sup> dyn/cm <sup>2</sup> )	8.329	8.842	/

4.526

TABLE I
PARAMETERS USED IN MODELING OF InAs/GaSb SLs Devices [22], [23], [24]

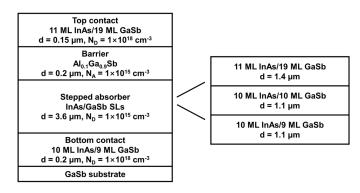
In this article, due to the tunability of electron and hole minibands by modifying the thickness of constituent layers, an nBn InAs/GaSb T2SLs MWIR photodetector with a stepped absorber is proposed to enhance the extraction of photogenerated carriers from the active layers. Due to the miniband offsets, an electric field is introduced in the stepped absorber, which promotes the carrier transport, improving the peak QE, responsivity, and specific detectivity  $(D^*)$ . In addition,  $D^*$  can be further improved by increasing the thickness of the stepped absorber layers.

 $C_{12}$  (10<sup>11</sup> dyn/cm<sup>2</sup>)

# II. SIMULATION PROCEDURE

The simulations were performed by using APSYS software from Crosslight Inc. The zincblende  $8 \times 8$  kp model was used to calculate the subband structures, in which an envelope function approximation formalism was employed [23]. The states throughout the Brillouin zone were evaluated. The optical properties of SLs were calculated based on the Fermi's golden rule. Following that, the Poisson equation and continuity equation were applied to monitor the complex light absorption and carrier dynamics in the detectors. The parameters of varied materials used in the simulation are listed in Table I. In addition, the lifetimes of both electron and hole are 50 ns [25], and the mobilities of electron and hole are 3000 and  $600 \text{ cm}^2 \cdot \text{V}^{-1} \cdot \text{s}^{-1}$  [26], respectively.

The schematic of the nBn InAs/GaSb SLs photodetector with a stepped absorber (S1) is shown in Fig. 1. It consists of a 0.2- $\mu$ m-thick 10-ML InAs/9-ML GaSb SLs n-type bottom contact layer on a GaSb substrate. Following is the 3.6- $\mu$ m-thick stepped absorber, which is composed of a 1.1- $\mu$ m-thick 10-ML InAs/9-ML GaSb SLs, a 1.1- $\mu$ m-thick 10-ML InAs/10-ML GaSb SLs, and a 1.4- $\mu$ m-thick 11-ML InAs/19-ML GaSb SLs. Finally, a 0.2- $\mu$ m-thick Al<sub>0.1</sub>Ga<sub>0.9</sub>Sb layer is chosen as the barrier, followed by a 0.15- $\mu$ m-thick



4.026

Fig. 1. Schematic of an nBn InAs/GaSb SLs device with a stepped absorber (S1).

11-ML InAs/19-ML GaSb SLs top contact. Three nBn detectors with different uniform absorbers (10-ML InAs/9-ML GaSb, 10-ML InAs/10-ML GaSb, and 11-ML InAs/19-ML GaSb SLs) are considered as references and the structures of detectors are listed in Table II.

For InAs/GaSb SLs, the electronic position of minibands can be tuned by changing the thickness of constituent layers. The effective miniband gaps of artificial SLs are determined by the lowest electron minibands and the highest hole minibands. As shown in Fig. 2, for 10-ML InAs/9-ML GaSb SLs, the miniband gap is ~234 meV. Increasing the GaSb thickness from 9 to 10 ML would slightly widen the effective miniband gap to ~235 meV. Since the holes are almost confined in the GaSb, the top of HH1 increases with the thickening of the GaSb layer. With increasing the GaSb to InAs ratio and period thickness, the effective miniband gap is reduced to ~220 meV for 11-ML InAs/19-ML GaSb SLs. Meanwhile, the joint density of states for electrons and holes get more dispersed, and a reduction in the absorption coefficient and a red shift

,	<b>Bottom contact</b>	Absorber	Barrier	Top contact
	d=0.2 μm	d=3.6 μm	d=0.2 μm	d=0.15 μm
	$N_D = 1 \times 10^{18} \text{ cm}^{-3}$	$N_D = 1 \times 10^{15} \text{ cm}^{-3}$	$N_A = 1 \times 10^{15} \text{ cm}^{-3}$	$N_D = 1 \times 10^{18} \text{ cm}^{-3}$
S1	10 ML InAs/9 ML GaSb	Stepped absorber	Al <sub>0.1</sub> Ga <sub>0.9</sub> Sb	11 ML InAs/19 ML GaSb
U1	10 ML InAs/9 ML GaSb	10 ML InAs/9 ML GaSb	$Al_{0.1}Ga_{0.9}Sb$	10 ML InAs/9 ML GaSb
<b>U2</b>	10 ML InAs/10 ML GaSb	10 ML InAs/10 ML GaSb	$\mathrm{Al}_{0.1}\mathrm{Ga}_{0.9}\mathrm{Sb}$	10 ML InAs/10 ML GaSb
U3	11 ML InAs/19 ML GaSb	11 ML InAs/19 ML GaSb	$Al_{0.1}Ga_{0.9}Sb$	11 ML InAs/19 ML GaSb

TABLE II
STRUCTURES OF FOUR InAs/GaSb SLs Devices

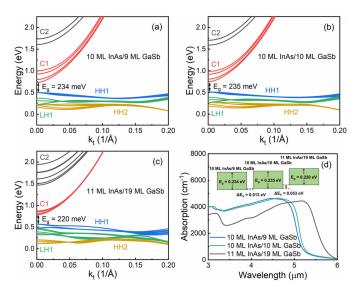


Fig. 2. Energy dispersion diagrams of (a) 10-ML InAs/9-ML GaSb, (b) 10-ML InAs/10-ML GaSb, and (c) 11-ML InAs/19-ML GaSb SLs at 150 K, and the zero energy reference is chosen as the valence band edge of InAs. (d) Absorption coefficients of three InAs/GaSb SLs at 150 K. Inset: Schematic band alignment of three InAs/GaSb SLs.

of the light absorption spectrum are expected [27], [28]. Due to the weak overlap of electron wave functions, a decrease in the conduction bandwidth ( $\Delta C1$ ) as well as an increase in the bottom of C1 is obtained in thick SL periods [29]. Consequently, due to the discontinuity of the conduction and valence minibands of the three InAs/GaSb SLs, an electric field can be introduced by applying a stepped absorber [30].

In device S1, the three adopted InAs/GaSb SLs share similar miniband gaps of  $\sim$ 0.230 eV ( $\sim$ 5.5  $\mu$ m) at 150 K. The absorption coefficients of the three InAs/GaSb SLs are  $\sim$ 4600 cm<sup>-1</sup> in the MWIR regions, which are consistent with previous experimental results [28], [31], [32].

# III. DEVICE PERFORMANCE AND ANALYSIS

The voltage-dependent QE (QE versus V) and wavelength-dependent QE (QE versus  $\lambda$ ) results are plotted in Fig. 3(a) and (b), respectively. The quantum efficiencies of devices increase with the reverse bias voltage and get saturated at about -0.2 V. Device S1 shows the highest QE in the wavelength region from 3.0 to 5.0  $\mu$ m under -0.2 V reverse bias at 150 K indicating an enhanced carrier extraction efficiency with the stepped absorber. The maximum QE of S1 reaches  $\sim$ 46% at 4.7  $\mu$ m, which is  $\sim$ 16% higher than all the three reference devices with a

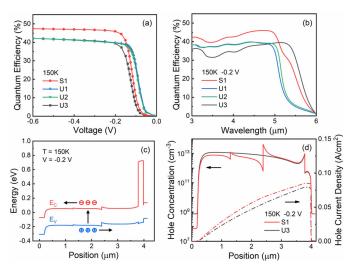


Fig. 3. (a) QE versus voltage of four devices. (b) QE versus wavelength of four devices. (c) Energy band diagram under bias of S1. (d) Hole concentration and hole current density of S1 and U3.

uniform absorber. Within the wavelength range from 3.0 to 5.0  $\mu$ m, the light absorption coefficient of 11-ML InAs/19-ML GaSb SLs is lower than that of 10-ML InAs/9-ML GaSb SLs and 10-ML InAs/10-ML GaSb SLs, resulting in a lowest QE in device U3. Due to different cutoff wavelengths of varied InAs/GaSb SLs profiles [as shown in Fig. 2(d)], a red shift in the QE spectra of U3 is observed, and the maximum QE of  $\sim$ 39% is obtained at 5.2  $\mu$ m. For S1, due to the different bandgaps and light absorption coefficients of the three adopted InAs/GaSb SLs, the cutoff edge in the long wavelength region is not as steep as the other three devices. Because of lower valence band offsets at absorber/barrier interfaces, the QEs of U1 and U2 could get saturated under a smaller reverse bias. Considering the response spectrum, U3 is chosen as the main reference device in the subsequent discussion.

The energy band alignment, the hole concentration, and hole current density distribution in the devices under -0.2 V bias and illumination are illustrated in Fig. 3(c) and (d). Due to the valence band and conduction band offsets between the three InAs/GaSb SLs, an electric field is generated, resulting in lower hole density in device S1. The electric field in the stepped absorber of S1 can effectively promote the transport of photogenerated carriers. Therefore, device S1 exhibits higher photocurrent and improved QE, which is consistent with our results.

The temperature-dependent dark current density  $(J_d)$  versus voltage curves are illustrated in Fig. 4(a). The  $J_d$  of both

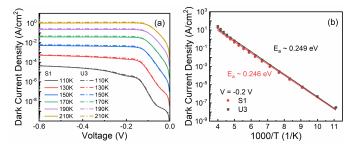


Fig. 4. (a) Dark current density as a function of applied bias voltage for S1 and U3 with temperatures ranging from 110 to 210 K and (b) Arrhenius plots of the dark current density under -0.2 V bias. Solid lines represent the linear fit at different temperatures.

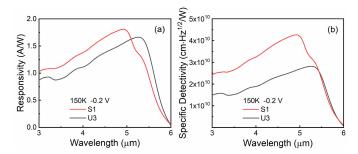


Fig. 5. (a) Responsivity and (b) specific detectivity of S1 and U3 at 150 K and under -0.2 V bias voltage.

devices rises sharply with the increasing temperature due to the increased intrinsic carrier density, and the  $J_d$  of S1 is slightly lower than U3. At 150 K and under -0.2 V bias voltage, the  $J_d$  values of S1 and U3 are  $\sim 3.9 \times 10^{-3}$  and  $\sim 4.8 \times 10^{-3}$  A/cm², respectively. When the reverse bias voltage exceeds -0.2 V, the  $J_d$  values reach a plateau of  $\sim 5.1 \times 10^{-3}$  A/cm² for S1 and  $\sim 6.2 \times 10^{-3}$  A/cm² for U3. The hole density in S1 is lower than that in U3, which may be responsible for the lower dark current in U3, which may be responsible for the lower dark current in U3, which may be responsible for the lower dark current in U3, which may be responsible for the lower dark current in U3, which may be responsible for the lower dark current in U3, which may be responsible for the lower dark current in U3, which may be responsible for the lower dark current in U3, which may be responsible for the lower dark current in U3, which may be responsible for the lower dark current in U3, which may be responsible for the lower dark current in U3, which may be responsible for the lower dark current in U3, which may be responsible for the lower dark current in U3, which may be responsible for the lower dark current in U3, which may be responsible for the lower dark current in U3, which may be responsible for the lower dark current in U3, which may be responsible for the lower dark current in U3, which may be responsible for the lower dark current in U3, which may be responsible for the lower dark current in U3, which may be responsible for the lower dark current in U3, which may be responsible for U3. It indicates that the dark currents of both devices are dominated by the carrier diffusion mechanism [34].

The 50% cutoff wavelengths of S1 and U3 are 5.5 and 5.7  $\mu$ m, respectively, as illustrated in Fig. 5(a). At 150 K and under -0.2 V bias voltage, the maximum R is  $\sim$ 1.81 A/W at 4.9  $\mu$ m for S1, which is  $\sim$ 9% higher than the U3 where the maximum R is  $\sim$ 1.66 A/W at 5.3  $\mu$ m. Accordingly, as shown in Fig. 5(b), the maximum specific detectivity ( $D^*$ ) of S1 reaches  $\sim$ 4.26  $\times$  10<sup>10</sup> cm·Hz<sup>1/2</sup>/W at 4.9  $\mu$ m, which is  $\sim$ 53% higher than that of  $\sim$ 2.79  $\times$  10<sup>10</sup> cm·Hz<sup>1/2</sup>/W at 5.3  $\mu$ m for U3 at 150 K and -0.2 V bias voltage. With similar 50% cutoff wavelengths, S1 exhibits higher  $D^*$  in nearly the entire MWIR region.

The dark current density has an almost linear relationship with the thickness of absorber layer, which in return is directly associated with the light absorption in the device [7]. Therefore, a tradeoff between photogenerated carriers and dark current density is essential in high-performance detectors. *U*3 exhibits optimal performance with a uniform absorber

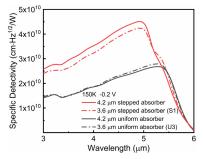


Fig. 6. Specific detectivity of S1 and U3 with varied absorber thicknesses for  $T=150~{\rm K}$  and  $V=-0.2~{\rm V}$ .

layer thickness of 3.6  $\mu$ m. Increasing the thickness of uniform absorber from 3.6 to 4.2  $\mu$ m would not bring about an improvement in QE due to the limited carrier diffusion length of InAs/GaSb SLs [21]. On the contrary, a reduction in  $D^*$  of the device with a 4.2- $\mu$ m uniform absorber is observed as the  $J_d$  rises, as illustrated in Fig. 6. In S1, increasing the total thickness of the stepped absorber from 3.6 to 4.2  $\mu$ m, which consists of a 1.5- $\mu$ m-thick 10-ML InAs/11-ML GaSb, a 1.5- $\mu$ m-thick 10-ML InAs/10-ML GaSb, and a 1.2- $\mu$ m-thick 11-ML InAs/19-ML GaSb SLs, the maximum  $D^*$  can be further increased to  $\sim$ 4.51  $\times$  10<sup>10</sup> cm·Hz<sup>1/2</sup>/W at 4.9  $\mu$ m. Benefiting from the improved carrier transport in S1 by applying a stepped absorber, it provides a feasible method to further improve the performance of InAs/GaSb SLs infrared detectors.

### IV. CONCLUSION

In summary, we have provided an insight of the InAs/GaSb SLs stepped absorber. The stepped absorber is proposed to enhance the carrier extraction from the absorber layers. The energy band alignments and optical properties of InAs/GaSb SLs with various periods are studied. As a result of the improvement of hole transport, the device with a stepped absorber exhibits a higher maximum OE of ~46% at 4.7  $\mu$ m under -0.2 V bias at 150 K. The maximum  $D^*$  of the device with a stepped absorber is improved to  $\sim 4.26 \times 10^{10}$  cm·Hz<sup>1/2</sup>/W at 4.9  $\mu$ m, which is  $\sim 53\%$ higher than the device with a uniform absorber. Furthermore, benefiting from the more efficient carrier extraction, increasing the total thickness of the stepped absorber from 3.6 to 4.2  $\mu$ m, the maximum  $D^*$  of detector can be further increased to  $\sim$ 4.51  $\times$  10<sup>10</sup> cm·Hz<sup>1/2</sup>/W. A feasible method is proposed to further improve the performance of InAs/GaSb SLs infrared detectors.

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